

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	0	(((silicon semiconductor) near5 (film layer)) and (substrate wafer) and ((laser near5 light) near8 crystalliz\$3 near8 air) and ((etch\$3 remov\$3) near5 oxide)) and recrystalliz\$3 and (gate near5 (inuslat\$3 dielectric) and (source drain impurity dopant ion implant\$3 dop\$3)).clm.	US-PGPU B	OR	ON	2007/05/25 11:03
L2	2	(((silicon semiconductor) near5 (film layer)) and (substrate wafer) and ((laser near8 crystalliz\$3 near8 air) and ((etch\$3 remov\$3) near5 oxide)).clm.	US-PGPU B	OR	ON	2007/05/25 11:05